

Docket No. 5000-5291

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): Takefumi NISHIMUTA; Hiroshi MIYAGI; Tadahiro OHMI; Shigetoshi SUGAWA; and Akinobu TERAMOTO

Serial No.: TBA Group Art Unit: TBA

Filed: Herewith Examiner: TBA

For: MIS TRANSISTOR AND CMOS TRANSISTOR

Customer No.: 27123

**INFORMATION DISCLOSURE STATEMENT**

Mail Stop  
Commissioner for Patents  
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Alexandria, VA 22313-1450

Sir:

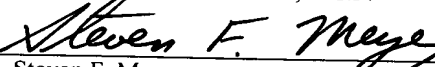
Pursuant to Rule 56, applicant hereby calls the attention of the Patent Office to the references listed on the attached Form PTO 1449. Copy(ies) of these references ☒ are attached ☐ were filed in related application U.S. Serial No(s) \_\_\_\_\_, filed \_\_\_\_\_, respectively.

- ☐ This document is being filed within three (3) months of the filing date of the application
- ☐ Please charge the \$180 fee to Deposit Account No. 13-4500, Order No. \_\_\_\_\_.
- ☒ This document is being concurrently filed with the above-identified application
- ☐ This document is being concurrently filed with an Request for Continued Examination (RCE)
- ☐ This document is being filed prior to a first Office Action
- ☒ This document is accompanied by a Search Report/Communication cited in a corresponding PCT or foreign counterpart application.
- ☒ The Commissioner is hereby authorized to charge any additional fees which may be required for this Information Disclosure Statement, or credit any overpayment to Deposit Account No. 13-4500, Order No. 5000-5291. A DUPLICATE COPY OF THIS SHEET IS ATTACHED.

Respectfully submitted,  
MORGAN & FINNEGAN, L.L.P.

Dated: December 13, 2005

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<b>FORM PTO-1449</b>  <b>INFORMATION DISCLOSURE</b> <b>CITATION</b>			Attorney Docket No. 5000-5291		Serial No.: To Be Assigned	
			Applicants: Takefumi NISHIMUTA; Hiroshi MIYAGI; Tadahiro OHMI; Shigetoshi SUGAWA; and Akinobu TERAMOTO			
			Filing Date: Herewith		Group Art Unit: To Be Assigned	
<b>U.S. PATENT DOCUMENTS</b>						
<b>Examiner Initial</b>	<b>Patent Number</b>	<b>Publication Date</b>	<b>Name</b>	<b>Class</b>	<b>Sub-Class</b>	<b>Filing Date</b>
	2002/0185676	December 12, 2002	Momose	257	327	July 30, 2001
	2004/0102052	May 27, 2004	Ohmi et al	438	765	December 27, 2001
<b>FOREIGN PATENT DOCUMENTS</b>						
<b>Examiner Initial</b>	<b>Patent Number</b>	<b>Publication Date</b>	<b>Country</b>	<b>Class</b>	<b>Sub-Class</b>	<b>Translation</b>
	2002-110963	April 12, 2002	JAPAN	H 01 L	29 / 78	Accompanied by English abstract
	2002-359293	December 13, 2002	JAPAN	H 01 L	21 / 8238	Accompanied by US Publication No. 2002/0185676
	8-264764	October 11, 1996	JAPAN	H 01 L	29 / 78	Accompanied by English abstract
	7-249768	September 26, 1995	JAPAN	H 01 L	29 / 78	Accompanied by English abstract
	2002-261091	September 13, 2002	JAPAN	H 01 L	21 / 316	Accompanied by US Publication No. 2004/0102052
	9-023011	January 21, 1997	JAPAN	H 01 L	29 / 786	Accompanied by English abstract
	63-228662	September 22, 1088	JAPAN	H 01 L	27 / 08	Accompanied by English abstract
	1-276669	November 7, 1989	JAPAN	H 01 L	29 / 78	Accompanied by English abstract
<b>OTHER DOCUMENTS (Including Author, Title, Date, etc.)</b>						
	Partial English translation of office action for corresponding Taiwanese Patent Application and Taiwanese Office Action.					
	Hisamoto et al, "FinFET - A Self-Aligned Double-Gate MOSFET Scalable to 20nm", <i>IEEE Transactions on Electron Devices</i> , Vol 47, No. 12, pps 2320-2325, December 12, 2000					
	Y. Choi et al, "FinFET Process Refinements for Improved Mobility and Gate Work Function Engineering", <i>Electron Devices Meeting, IEDM 02 Digest</i> , pps 259-262, December 2002					
	Y. Choi et al, "Nanoscale CMOS Spacer FinFET for the Terabit Era", <i>IEEE Electron Device Letters</i> , Vol 23, No. 1, pps 25-27, January 2002					
Examiner			Date Considered			
<b>EXAMINER:</b> Initial if reference considered, whether or not citation is in conformance with MPEP §609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.						